



SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name:	in Jelee	Examiner #: 76060	Date: 12-28-05
Art:Unit: 1752 Phone I	Number 30 2-1333	Serial Number:	10/248,228
Mail Box and Bldg/Room Location	n: 9660 Resi	ilts Format Preferred (circle):	PAPER DISK E-MAIL
If more than one search is subm	(Rem.)		

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc. if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.			
•	z. see Bi		
Inventors (please provide full names):			
mivements (pieuse provide run names)			
Earliest Priority Filing Date:		_	
For Sequence Searches Only Please inclui appropriate serial number.	le all pertinent information (p	parent, child, divisional, or issued pa	tent numbers) along with the
appropriate servas number.			
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0 40)		·
Plz. Search for from the 1	bllowing mo	nomer (1B)	t
or (10) of (1, #2			
· · ·		•	
in each of the formula (1B) and (1c),			
SCIENTIFIC REFERENCE BR	- Z or - \	′- ₹	
Sci P REFERENCE BR	CY = Imear	/branched alkyler	ne or
JAN 0 3 KCOU	monocyclic/polycyclic alkylene)		
J KCOU	•		tane, triamantane
Pal. & T.M. Office			
O/ICe		or mixtures	
·	(All atte	sched Page Br nantane and tr	the structures for
STAFF USE ONLY		~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~ ~	*****
Searcher:	Type of Search NA Sequence (#)	Vendors and cost whe	re applicable
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Date Searcher Picked Up:	Bibliographic	Dr.Link	·
Date Completed:	Litigation	Lexis/Nexis	· · · · · · · · · · · · · · · · · · ·
earcher Prep & Review Time:	*Fulltext	'Sequence' Systems	•
Clerical Prep Time:	Patent Family	-WWW/Internet	
Online Time:	Other	Other (specify)	<u> </u>
TO-1590 (8-01)			

=> file reg FILE 'REGISTRY' ENTERED AT 17:42:00 ON 04 JAN 2006 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2006 American Chemical Society (ACS)

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FILE 'LREGISTRY' ENTERED AT 17:23:31 ON 04 JAN 2006 E DIAMANTANE/CN

FILE 'REGISTRY' ENTERED AT 17:23:59 ON 04 JAN 2006

E DIAMANTANE/CN

L1 1 S E3

E TRIAMANTANE/CN

L2 1 S E3

FILE 'LREGISTRY' ENTERED AT 17:24:39 ON 04 JAN 2006

L3 STR 2292-79-7

FILE 'REGISTRY' ENTERED AT 17:31:28 ON 04 JAN 2006

L4 0 S L3

E 2395.1.1/RID

L5 713 S E3

E 4790.1.1/RID

L6 58 S E3

L7 248 S L5 AND PMS/CI

L8 0 S L3 FUL

FILE 'HCAPLUS' ENTERED AT 17:38:12 ON 04 JAN 2006

L9 243 S DAMMEL R?/AU

L10 11751 S PHOTORESIST?/TI

L11 64 S L9 AND L10

SEL L11 1-64 RN

FILE 'REGISTRY' ENTERED AT 17:38:46 ON 04 JAN 2006

L12 276 S E1-E276

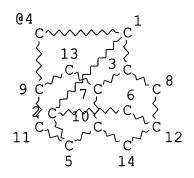
L13 3 S L12 AND (L5 OR L6)

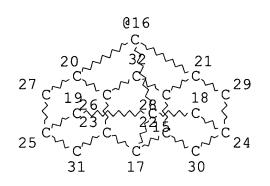
FILE 'HCA' ENTERED AT 17:40:11 ON 04 JAN 2006

L14 1 S L13

FILE 'REGISTRY' ENTERED AT 17:42:00 ON 04 JAN 2006

=> d 18 que stat L3 STR





 $C = C \sim G1$ 33 34 35 SO2~G2 038 39 G3 42

VAR G1=0/38VAR G2=N/OVAR G3=4/16NODE ATTRIBUTES: DEFAULT MLEVEL IS ATOM DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:

RING(S) ARE ISOLATED OR EMBEDDED

NUMBER OF NODES IS 38

STEREO ATTRIBUTES: NONE

L8O SEA FILE=REGISTRY SSS FUL L3

100.0% PROCESSED 66649 ITERATIONS

SEARCH TIME: 00.00.01

Answers

=> file hca

FILE 'HCA' ENTERED AT 17:42:13 ON 04 JAN 2006 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

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=> d l14 1 all hitstr

L14 ANSWER 1 OF 1 HCA COPYRIGHT 2006 ACS on STN

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ΑN
     143:123042 HCA
                  04 Aug 2005
ED
     Entered STN:
TI
     Photoresist composition
     Dammel, Ralph R.
IN
PΑ
     USA
SO
     U.S. Pat. Appl. Publ., 23 pp.
     CODEN: USXXCO
DT
     Patent
LA
     English
     ICM G03C001-76
IC
INCL 430270100
CC
     74-5 (Radiation Chemistry, Photochemistry, and Photographic and
     Other Reprographic Processes)
     Section cross-reference(s): 35, 38
FAN.CNT 1
                                    APPLICATION NO.
     PATENT NO.
                        KIND
                               DATE
                                                                 DATE
                                          ____
                               20050707
PI
     US 2005147915
                         Α1
                                           US 2003-748778
                                                                 200312
                                                                 29
                                         WO 2004-IB4384
     WO 2005066714
                         Α2
                               20050721
                                                                 200412
                                                                  08
            AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA,
        W:
            CH, CN, CO, CR, CU, CZ, DK, DM, DZ, EC, EE, EG, ES, FI, GB,
            GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR,
            KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX,
            MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE,
            SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN,
            YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW,
            AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ,
            DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC,
            NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA,
            GN, GQ, GW, ML, MR, NE, SN, TD, TG
PRAI US 2003-748778
                        Α
                              20031229
CLASS
                CLASS
 PATENT NO.
                       PATENT FAMILY CLASSIFICATION CODES
                       ______
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                ____
 US 2005147915
                ICM
                       G03C001-76
                INCL
                       430270100
                IPCI
                       G03C0001-76 [ICM, 7]
                NCL
                       430/270.100
                ECLA
                       G03F007/039C1S
 WO 2005066714
                IPCI
                       G03F0007-00 [ICM,7]
                ECLA
                       G03F007/039C1S
AB
     The present invention relates to a photosensitive compn. useful at
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wavelengths between 300 nm and 10 nm which comprises a polymer contg. a substituted or unsubstituted higher adamantane.

ST photoresist compn higher adamantane

IT Photoresists

(photoresist compn. contg. substituted or unsubstituted higher adamantane)

IT 24937-72-2P, Maleic anhydride homopolymer 177080-67-0DP, 2-Methyl-2-adamantyl methacrylate, polymer with hydroxydiamantane methacrylate and butyrolactone methacrylate 195000-66-9DP, polymer with hydroxydiamantane methacrylate and Me adamantane methacrylate and/or Me diamantane methacrylate 857284-47-0DP, polymer with butyrolactone methacrylate and hydroxydiamantane methacrylate derivs. 857284-49-2P 857284-60-7P

(photoresist compn. contg. substituted or unsubstituted higher adamantane)

857284-47-ODP, polymer with butyrolactone methacrylate and hydroxydiamantane methacrylate derivs. 857284-49-2P 857284-60-7P

(photoresist compn. contg. substituted or unsubstituted higher adamantane)

RN 857284-47-0 HCA

CN 2-Propenoic acid, 2-methyl-, decahydro-2-methyl-3,5,1,7[1,2,3,4]butanetetraylnaphthalen-2-yl ester (9CI) (CA INDEX NAME)

RN 857284-49-2 HCA

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with decahydro-2-methyl-3,5,1,7[1,2,3,4]butanetetraylnaphthalen-2-yl 2-methyl-2-propenoate, 2,5-furandione and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 857284-47-0 CMF C19 H26 O2

CM 2

CRN 195000-66-9 CMF C8 H10 O4

CM 3

CRN 154970-45-3 CMF C12 H18 O2

CM 4

CRN 108-31-6 CMF C4 H2 O3

RN 857284-60-7 HCA

CN 2-Propenoic acid, 2-methyl-, decahydro-2-methyl-3,5,1,7[1,2,3,4]butanetetraylnaphthalen-2-yl ester, polymer with
3-hydroxytricyclo[3.3.1.13,7]dec-1-yl 2-methyl-2-propenoate and
tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 857284-47-0 CMF C19 H26 O2

CM 2

CRN 195000-66-9 CMF C8 H10 O4

CM 3

CRN 115372-36-6 CMF C14 H20 O3